

Supplementary Information

Enhanced Lithographic Performance of Polymer-Bound PAG Photoresists Synthesized via RAFT Polymerization

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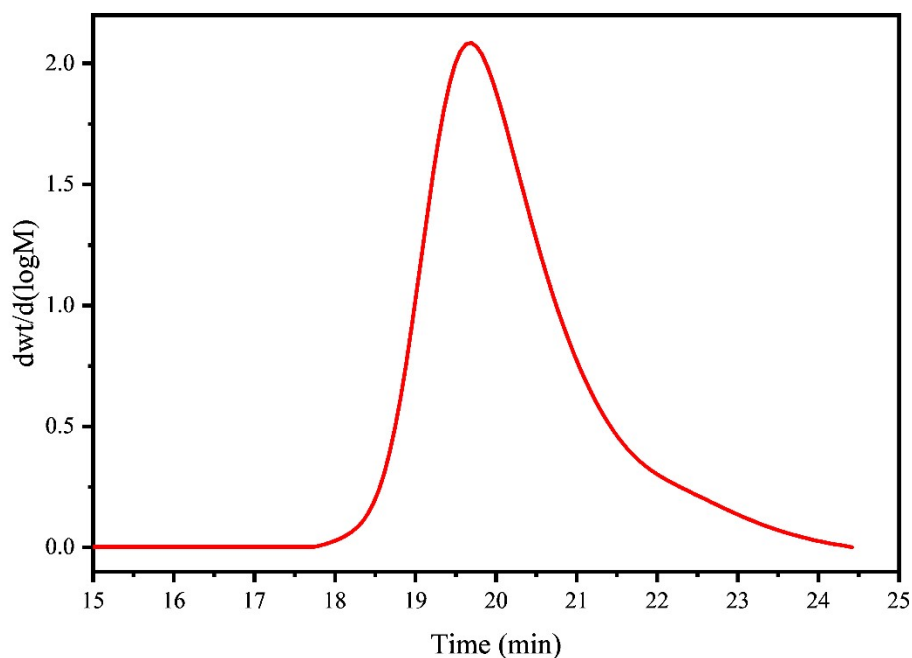


Figure S1 GPC image of PTIMV₀

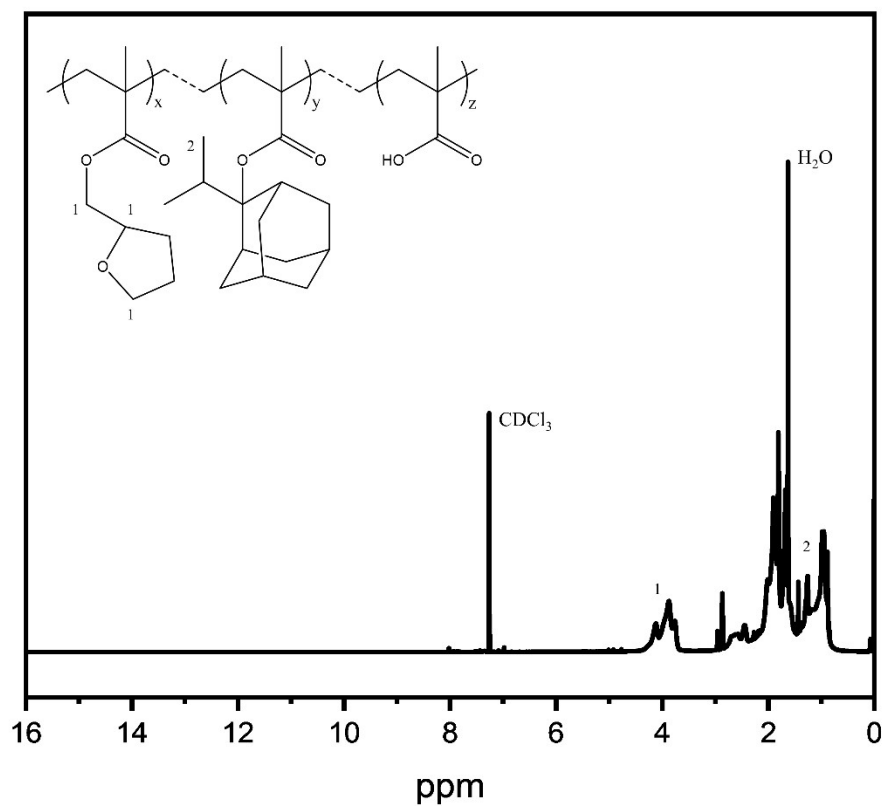


Figure S2 ^1H NMR spectra of PTIMV₀

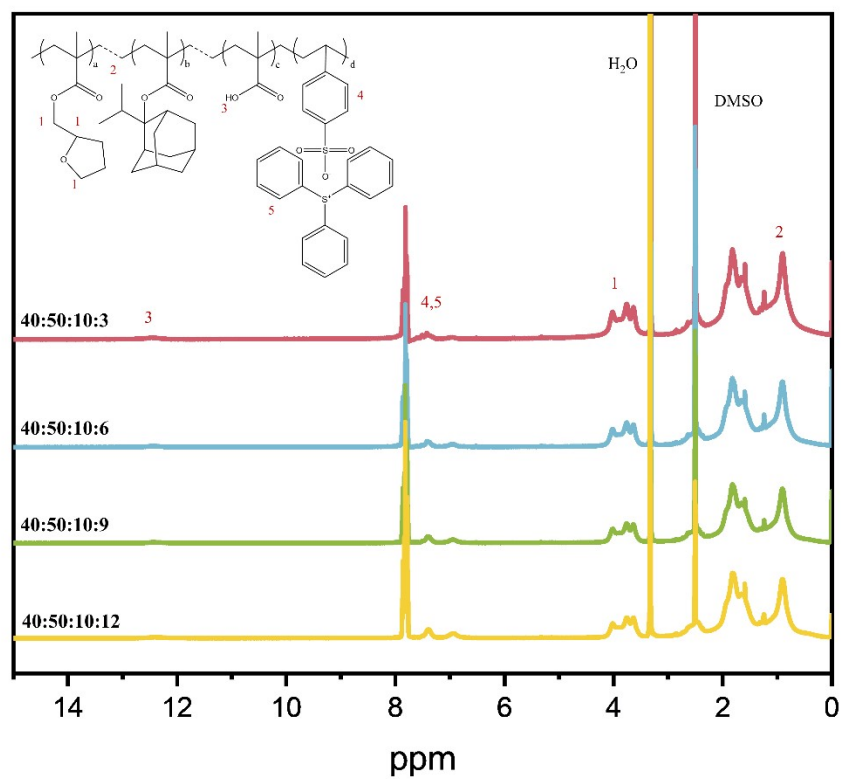


Figure S3 ^1H NMR spectra of PTIMVs